

**NEW UTILITY PATENT APPLICATION
TRANSMITTAL***(Only for new nonprovisional applications under 37 C.F.R. 1.53(b))*Docket No.
M4065.0184/P184Total pages in this
submission**TO THE ASSISTANT COMMISSIONER FOR PATENTS****Box Patent Application
Washington, D.C. 20231**

Transmitted herewith for filing under 35 U.S.C. 111(a) and 37 C.F.R. 1.53(b) is a new utility patent application for an invention entitled:

SEMICONDUCTOR DEVICE PACKAGE AND METHOD

and invented by:

Alan G. Wood and Larry D. Kinsman

IF A CONTINUATION APPLICATION, check appropriate box and supply requisite information:☐

Continuation

☐

Divisional

☐

Continuation-in-part (CIP) of prior application No.:

Enclosed are:

Application Elements

1. ☒ Filing fee as calculated and transmitted as described below
2. ☒ Specification having 16 pages(s) and including the following:
 - a. ☒ Descriptive title of the invention
 - b. ☐ Cross references to related applications *(if applicable)*
 - c. ☐ Statement regarding Federally-sponsored research/development *(if applicable)*
 - d. ☐ Reference to microfiche appendix *(if applicable)*
 - e. ☒ Background of the invention
 - f. ☒ Brief summary of the invention
 - g. ☒ Brief description of the drawings *(if drawings filed)*
 - h. ☒ Detailed description
 - i. ☒ Claims as classified below
 - j. ☒ Abstract of the disclosure

Application Elements (continued)

3. ☒ Drawing(s) (when necessary as prescribed by 35 U.S.C. 113)
☐ Formal ☒ Informal Number of sheets: 5
4. ☒ Oath or Declaration
a. ☒ Newly executed (original or copy) ☐ Unexecuted
b. ☐ Copy from a prior application (37 C.F.R. 1.63(d) (for continuation/divisional applications only)
c. ☐ With Power of Attorney ☒ Without Power of Attorney
5. ☐ Incorporation by reference (usable if Box 4b is checked)
The entire disclosure of the prior application, from which a copy of the oath or declaration is supplied under Box 4b, is considered as being part of the disclosure of the accompanying application and is hereby incorporated by reference therein.
6. ☐ Computer program in microfiche
7. ☐ Genetic sequence submission (if applicable, all must be included)
a. ☐ Paper copy
b. ☐ Computer readable copy
c. ☐ Statement verifying identical paper and computer readable copies

Accompanying Application

8. ☒ Assignment papers (cover sheet & document(s))
9. ☒ 37 C.F.R. 3.73(b) statement (when there is an assignee)
10. ☐ English translation document (if applicable)
11. ☐ Information Disclosure Statement/PTO-1449 ☐ Copies of IDS citations
12. ☐ Preliminary Amendment
13. ☒ Acknowledgment postcard
14. ☐ Certified copy of priority document(s) (if foreign priority is claimed)
15. ☐ Certificate of Mailing
☐ First Class ☐ Express Mail (Label No.: _____)
16. ☐ Small Entity statement(s) -- # submitted _____ (if Small Entity status claimed)

Accompanying Application (continued)

- 17.
- ☐
- Additional enclosures (please identify below):

Fee Calculation and Transmittal

The filing fee for this utility patent application is calculated and transmitted as follows:

☒ Large Entity ☐ Small Entity

<u>CLAIMS AS FILED</u>						
For	# Filed	# Allowed	# Extra	Rate	Fee	
Total Claims	38	- 20 =	18	x \$18.00	\$324.00	
Independent Claims	5	- 3 =	2	x \$78.00	\$156.00	
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>						
Other Fees (specify purpose): Recordation Form Cover Sheet					\$40.00	
BASIC FEE					\$690.00	
TOTAL FILING FEE					\$1,210.00	

☒ A check in the amount of \$1,210.00 to cover the total filing fee is enclosed.☒ The Commissioner is hereby authorized to charge and Deposit Account No. 4 - 1073 as described below. A duplicate copy of this sheet is enclosed.☐ Charge the amount of _____ as filing fee.☒ Credit any overpayment.☒ Charge any additional filing fees required under 37 C.F.R. 1.16 and 1.17.☐ Charge the issue fee set in 37 C.F.R. 1.18 at the mailing of the Notice of Allowance, pursuant to 37 C.F.R. 1.31(b).Dated: June 16, 2000

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
APPLICATION FOR U.S. LETTERS PATENT

Title:

SEMICONDUCTOR DEVICE PACKAGE AND METHOD

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SEMICONDUCTOR DEVICE PACKAGE AND METHOD

FIELD OF THE INVENTION

5 The present invention relates to a method of packaging semiconductor devices. The present invention also relates to semiconductor device packages, including ball grid array (BGA) packages.

BACKGROUND OF THE INVENTION

10 A method of making ball grid array packages is described in U.S. Patent Application No. 09/317,957, filed May 25, 1999. According to that method, individual semiconductor devices are attached to a patterned strip, and then the devices are electrically connected to ball grid arrays on the opposite side of the strip, and then the strip is segmented to produce
15 finished packages. A disadvantage associated with the method described in the '957 application is that each semiconductor device must be individually positioned with respect to the strip. The devices are spaced apart from each other along the length of the strip. Consequently, a separate alignment step is required for each package. In addition, since the semiconductor devices are separated from each other before they are connected to the ball
20 grid arrays, the devices must be tested and burned-in separately. The entire disclosure of U.S. Patent Application No. 09/317,957 is expressly incorporated herein by reference.

 Another method of making ball grid array packages is described in U.S. Patent No. 5,858,815 (Heo). According to the Heo method, a wafer is attached to a film such that bond
25 pads are exposed through openings in the film, and then the bond pads are connected to solder balls on the opposite side of the film, and then the layered assembly is sawed into chip-sized packages. There are numerous disadvantages associated with the Heo method. Among them is that the packages do not have sufficient stiffness. In addition, the prior art does not provide a satisfactory method of testing the Heo packages, and the prior art does not provide a
30 suitable method of aligning the wafer with respect to the film.

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SECTION 27-0132

The term "ball grid array" is used herein in a broad sense to include fine pitch ball grid arrays (FBGAs) within its definition.

SUMMARY OF THE INVENTION

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The present invention overcomes many of the disadvantages of the prior art. The present invention relates to a method of making semiconductor device packages. The method includes the steps of forming a layered assembly by attaching a wafer to a dielectric layer, testing semiconductor devices in the wafer, and then dicing the layered assembly. The dielectric layer may be, for example, a flexible tape. The semiconductor devices may be chips containing integrated circuits or memory devices. The dicing operation may be performed by a circular saw or by another suitable dicing apparatus.

According to one aspect of the invention, the semiconductor devices are connected to input/output devices on the dielectric layer, before the testing and dicing steps. The input/output devices may be ball grid arrays (BGA) for board-on-chip (BOC) packages, if desired. The full wafer testing may be conducted through the ball grid arrays.

According to another aspect of the invention, defective packages identified during the testing step may be marked, segregated from the other packages, and discarded. The present invention should not be limited, however, to the specific methods and devices described in detail herein.

According to another aspect of the invention, a metal sheet may be included in the layered assembly before the testing and dicing steps. The metal sheet forms stiff metal layers in each of the finished packages. The metal layers may be used as heat spreaders and/or as electrical ground planes.

If desired, wire bonds may be used to connect the semiconductor devices to the ball grid arrays. In another embodiment of the invention, flip chip bumps on the semiconductor devices and conductive vias in the dielectric substrates are used to connect the semiconductor

devices to the ball grid arrays. In either case, the electrical connections may be made after the wafer is adhered to the dielectric tape and before the layered assembly is diced into separate finished packages.

5 Alignment of the wafer with respect to the dielectric tape may be accomplished by an optical device or by a magnetic system. In a preferred embodiment of the invention, the active components of all of the semiconductor devices are simultaneously aligned to the respective connection devices on the tape.

10 The present invention also relates to a ball grid array package formed of a semiconductor device and a dielectric substrate. The edges of the device and the substrate are formed by a common sawing operation and as a consequence are aligned with each other. The package may also be provided with a stiff metal layer. The package may be tested before it is singulated from a wafer-tape assembly.

15 These and other features and advantages of the invention will be more clearly understood from the following detailed description of the invention which is provided in connection with the accompanying drawings.

20 BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 is a cross-sectional view of a semiconductor device package constructed in accordance with the present invention.

25 FIG. 2 is partial top view of a wafer-tape assembly constructed in accordance with the present invention, showing multiple packages in an intermediate stage of manufacture.

FIG. 3 is a cross-sectional view of the assembly of FIG. 2, taken along the line 3-3.

30 FIG. 4 is a cross-sectional view of another semiconductor device package constructed in accordance with the present invention.

FIG. 5 is a perspective view of a package similar to the one shown in FIG. 4.

FIG. 6 is a cross-sectional view of another package constructed in accordance with the present invention.

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FIG. 7 is a cross-sectional view of yet another package constructed in accordance with the present invention.

FIG. 8 is a cross-sectional view of yet another package constructed in accordance with the present invention.

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FIG. 9 illustrates a magnetic system for aligning the wafer-tape assembly of FIGS. 2 and 3.

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FIG. 10 illustrates another magnetic alignment system constructed in accordance with the present invention.

DETAILED DESCRIPTION OF PREFERRED EMBODIMENTS

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Referring now to the drawings, where like reference numerals designate like elements, there is shown in FIG. 1 a semiconductor device package 10 constructed in accordance with one embodiment of the present invention. The package 10 has a semiconductor device 12, a dielectric substrate 14, and a ball grid array (BGA) 16. The semiconductor device 12 has an integrated circuit (not shown). A suitable adhesive 18 may be used to secure the semiconductor device 12 to the substrate 14. The semiconductor device 12 and the substrate 14 may be diced from a layered wafer-tape assembly 20 as described in more detail below in connection with FIG. 2. The dicing process causes the edges 22 of the substrate 14 to be aligned with the edges 24 of the semiconductor device 12.

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The ball grid array 16 may be used to mechanically and electrically connect the package 10 to a circuit board (not shown). Wire bonds 26, bond pads 28, circuit traces 30,

and ball pads 32 may be used to provide electrical communication between the semiconductor device 12 and the ball grid array 16. The wire bonds 26 extend through a slot-shaped opening 34. The traces 30 may be printed on the top surface 36 of the substrate 14 (before the semiconductor device 12 is adhered to the substrate 14). An insulative solder mask 38 extends over the traces 30. The mask 38 has openings 40 for receiving the individual balls of the ball grid array 16. A screen printing process may be used to apply the solder mask 38 as a paste to the entire surface of the substrate 14 except for the slot-shaped opening 34 and the ball pads 32. The wire bonds 26 and the bond pads 28 may be encapsulated in a suitable liquid encapsulant 42.

The substrate 14 may be a thin, flexible film. The film may be formed of a variety of dielectric materials, including for example FR-4/BT resins, epoxy, polyimide, KAPTON, UPLEX, and ceramic materials. The wire bonds 26 may be formed of gold, aluminum, copper or another suitable material. The traces 30 are formed of a conductive material such as copper, phosphor bronze, copper-nickel alloy, copper-nickel-tin alloy, or nickel-silver alloy. The adhesive 18 may be formed of a suitable die-attach material such as epoxy, resin, thermoplastic and/or elastomeric material. The ball grid array 16 may be formed of lead and/or tin. Alternatively, the ball grid array 16 may be formed of conductive polymer (metal suspended in a liquid). The present invention should not be limited to the specific materials and instrumentalities described in detail herein.

The wafer-tape assembly 20 shown in FIG. 2 is formed by aligning a silicon/semiconductor wafer 50 with respect to a slotted flexible tape 52. The wafer 50 contains many semiconductor devices 12. The tape 52 includes a corresponding number of slot-shaped openings 34. The bond pads 28 of the semiconductor devices 12 are aligned with the respective openings 34. (The bond pads 28, traces 30, and ball pads 32 are not shown in FIG. 2 for the sake of clarity of illustration.) Optical techniques may be used to achieve the desired alignment, and other suitable alignment methods are described below.

As shown in FIG. 3, the wafer 50 and the tape 52 are attached to each other by adhesive 18. The adhesive 18 may be screen printed onto the wafer 50 and/or the tape 52.

The bond pads 28 are not covered by the adhesive 18. The attachment of the wafer 50 to the tape 52 may be accomplished by applying heat and/or pressure to the layered assembly 20. Alternatively, a gas evacuation/purge process may be used to remove gas from between adjacent layers 50, 52 of the assembly 20.

Although a slotted tape 52 is shown in the drawings, the present invention should not be limited to the specific structures shown and described in detail herein. In an alternative embodiment of the invention, a circular dielectric sheet having the same diameter as the wafer 50 may be used to form the substrates 14.

After the wafer 50 is adhered to the tape 52, the wire bonds 26 are installed to connect the bond pads 28 of the semiconductor devices 12 to the respective traces 30 on the top surface 36 of the tape 52. The ball grid arrays 16 are then placed on the ball pads 32, and the encapsulant 42 may be molded over the slot-shaped openings 34. Then the semiconductor devices 12 may be tested and burned-in through the ball grid arrays 16. After the full wafer 50 is tested and burned in, the assembly 20 is diced to form the individual packages 10. The dicing process may be accomplished by sawing through the assembly 20 along lines defined by the edges 22, 24 of the semiconductor devices 12 and substrates 14.

An advantageous aspect of the present invention is the ability to determine the functionality of the packages 10 by full wafer testing and burning-in the entire wafer-tape assembly 20, rather than testing and burning-in singulated packages. Specifically, before the individual packages 10 are diced from the assembly 20, all of the packages 10 may be tested, through the respective ball grid arrays 16, by a suitable testing apparatus. If any package 10 is found to be defective, known electronic mapping apparatus and methodologies may be used to electronically mark the defective package(s) 10 such that, subsequent to the dicing operation, the defective package(s) 10 may be discarded or segregated from the non-defective packages 10.

FIG. 4 shows a semiconductor device package 60 constructed in accordance with another embodiment of the present invention. The package 60 has a metal layer 62 located

between the semiconductor device 12 and the substrate 14. In the illustrated embodiment, the substrate 14 is laminated to the metal layer 62. The metal layer 62 may be used to stiffen the package 60. In addition, the metal layer 62 may be used as a heat sink to dissipate heat from the semiconductor device 12, and the metal layer 62 also may be used as an electrical ground plane in the manner described in the '957 application. The metal layer 62 may be formed of copper, alloy-42 or another suitable material. Copper is a preferred material because it provides an adequate coefficient of thermal expansion (CTE) match to the other materials of the package 60. In addition, copper has excellent thermal and electrical properties (namely, high conductivity).

The package 60 may be singulated from a wafer-tape assembly of the type shown in FIGS. 2 and 3. With respect to the FIG. 4 embodiment, however, a metal sheet (not shown) is located between the wafer 50 and the tape 52 before the dicing operation. The metal layer 62 is singulated from the metal sheet when the assembly is diced (after full wafer testing). The metal sheet may cover all of the semiconductor devices 12 in the wafer 50. The dicing operation causes the edges 64 of the metal layer 62 to be aligned with the edges 22, 24 of the substrate 14 and the semiconductor device 12. As in the embodiment of FIGS. 1-3, plural packages 60 may be tested and burned-in before they are singulated from the layered assembly.

FIG. 6 shows a semiconductor device package 70 constructed in accordance with yet another embodiment of the present invention. The package 70 has a dielectric substrate 72 with metal-plugged vias 74. In contrast to the packages shown in FIGS. 1-5, the package 70 of FIG. 6 does not have a slot-shaped opening 34 or encapsulant 42. In the FIG. 6 embodiment, interior and exterior circuit traces 76, 78 are patterned on the top and bottom surfaces of the substrate 72 to provide electrical communication between the semiconductor device 12 and the ball pads 32.

The interior traces 76 make contact with flip chip bumps 80 on the active surface of the semiconductor device 12, and the exterior traces 78 are connected to the interior traces 76 through the vias 74. If desired, the bumps 80 may be formed of a tin/lead alloy (e.g., 63%

Sn/37% Pb). The bumps 80 may be reflowed to connect the semiconductor device 12 to the substrate 72. The area between the substrate 72 and the semiconductor device 12 may be underfilled with adhesive 18 or another suitable material, if desired. The diameter of each metal-plugged via 74 may be, for example, in a range from about 25 microns (0.001 inches) to about 200 microns (0.008 inches). The small vias 74 may be utilized to arrange a large number of circuits in a relatively small area.

As shown in FIG. 6, a solder mask 82 extends over the exterior traces 78. The mask 82 has openings 40 aligned with the ball pads 32 for receiving the solder balls and/or conductive bumps of the ball grid array 16. The mask 82 extends all the way across the central portion 84 of the substrate 72. Similarly to the FIGS. 1-5 embodiments, the package 70 shown in FIG. 6 may be singulated from a wafer-tape assembly. That is, the substrate 72 may be diced from a larger sheet of dielectric material (not shown) after the sheet is attached to a wafer 50, and after all of the packages 70 are tested and burned-in. The dicing operation causes the edges 24 of the semiconductor device 12 to be aligned with the edges 86 of the substrate 72.

If desired, a metal layer 90 (FIG. 7) may be attached to the semiconductor device 12 by a suitable adhesive 92. The thickness of the metal layer 90 may be in the range of from about 0.13 millimeters to about 0.25 millimeters. The metal layer 90 may operate as a heat sink or heat spreader to thermally stabilize the semiconductor device 12. In addition, the metal layer 90 may provide stiffness for the package 94. The metal layer 90 is preferably attached to the semiconductor device 12 before the device 12 is singulated from the wafer 50. This way, the metal layer 90 provides stiffness to the wafer-tape assembly prior to and during the dicing operation. The dicing operation causes the edges 96 of the metal layer 90 to be aligned with the edges 24, 86 of the semiconductor device 12 and the substrate 72.

According to an alternative embodiment of the invention, a thin layer of metal 91 (FIG. 8) is located on the back side of the semiconductor device 12. A layer of adhesive 92 is located between the thin layer of metal 91 and a thicker metal layer 90. The adhesive 92 may extend through the thin layer of adhesive 91 to provide adherence to the semiconductor

device 12. The thickness of the thin metal layer may be about 0.00254 millimeters. The product shown in FIG. 8 otherwise may be the same as the one shown in FIG. 7.

Referring now to FIG. 9, magnetic devices 100, 102 may be used to align the wafer 50 with respect to the dielectric tape 52. The devices 100, 102 may be oppositely charged (+/-) so that they are attracted to each other. The illustrated alignment method may be used to ensure that the die pads 28 of the wafer 50 are aligned with the corresponding openings 34 in the layered assembly 20 of FIGS. 2 and 3. FIG. 10 shows an alternative alignment method, in which a magnetic ring 104 is formed in the tape 52 and an oppositely charged slot 106 is formed in the wafer 50. The ring 104 is caused to center itself within the slot 106, such that the wafer 50 is adequately aligned with the tape 52 to form the assembly 20 of FIGS. 2 and 3. In an alternative embodiment of the invention, the ring 104 may be provided on the wafer 50 and the charged slot 106 may be formed in the dielectric tape 52. An advantage of the present invention is that a separate magnetic alignment system 100-106 is not required for each individual package 10, 60, 70, 94.

While the invention has been described in detail in connection with the preferred embodiments known at the time, it should be readily understood that the invention is not limited to such disclosed embodiments. Rather, the invention can be modified to incorporate any number of variations, alterations, substitutions or equivalent arrangements not heretofore described, but which are commensurate with the spirit and scope of the invention. Accordingly, the invention is not to be seen as limited by the foregoing description, but is only limited by the scope of the appended claims.

What is claimed as new and desired to be protected by Letters Patent of the United States is:

1. A method of making semiconductor device packages, comprising:
forming a layered assembly by attaching a wafer to a dielectric layer;
subsequently, testing semiconductor devices in said wafer; and
subsequently, dicing said layered assembly.

5

2. The method of claim 1, further comprising the step of connecting said
semiconductor devices to input/output devices on the dielectric layer.

3. The method of claim 2, wherein said testing is conducted through said
10 input/output devices.

4. The method of claim 3, further comprising the step of discarding one or more
defective packages.

5. The method of claim 1, wherein said step of forming said layered assembly
15 includes the step of adhering said wafer to said dielectric layer.

6. The method of claim 5, further comprising the step of electrically connecting
said semiconductor devices to ball grid arrays on said dielectric layer.

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7. The method of claim 6, wherein said connecting step comprises the step of
locating wire bonds in openings through said dielectric layer.

8. The method of claim 6, wherein said connecting step comprises the step of
25 connecting solder bumps on said wafer to circuit traces on said dielectric layer.

9. The method of claim 6, wherein said dicing step is performed by a saw.

10. The method of claim 6, further comprising the step of providing a metal layer
30 in said layered assembly.

11. A method of making semiconductor device packages, comprising:
forming a layered assembly by attaching a semiconductor wafer and a metal layer to
a dielectric layer;
connecting semiconductor devices in said semiconductor wafer to ball grid arrays
5 on said dielectric layer; and
subsequently, dicing said layered assembly.

12. The method of claim 11, wherein said forming step comprises the step of
adhering said wafer to said metal layer.

13. The method of claim 11, wherein said connecting step comprises the step of
locating wire bonds in openings in said dielectric layer.

14. The method of claim 13, further comprising the step of connecting said wire
15 bonds to conductive traces on said dielectric layer.

15. The method of claim 11, wherein said connecting step comprises the step of
connecting solder bumps on said wafer to conductive traces on said dielectric layer.

16. The method of claim 15, further comprising the step of connecting said traces
20 to conductive vias extending through said dielectric layer.

17. The method of claim 11, wherein said dicing step is performed by a saw.

18. The method of claim 11, further comprising the step of testing said
25 semiconductor devices through said ball grid arrays.

19. A method of making semiconductor device packages, comprising:
aligning a semiconductor wafer with respect to a dielectric tape;
subsequently, connecting semiconductor devices in said wafer to ball grid arrays on
said dielectric tape; and
5 simultaneously dicing said wafer and said dielectric tape.

20. The method of claim 19, wherein said wafer is optically aligned with respect to
said dielectric tape.

10 21. The method of claim 19, wherein said wafer is magnetically aligned with
respect to said dielectric tape.

22. The method of claim 21, wherein oppositely charged magnetic elements are
provided on said wafer and said tape.

15 23. The method of claim 21, further comprising the step of locating a magnetic
ring in a charged slot.

24. A semiconductor device package, comprising:
20 a semiconductor device having edges formed by a dicing operation;
a dielectric substrate having edges formed by said dicing operation;
a ball grid array on said dielectric substrate, said substrate being located between
said semiconductor device and said ball grid array; and
electrical connections between said semiconductor device and said ball grid array.

25 25. The package of claim 24, further comprising a metal layer having edges formed
by said dicing operation.

26. The package of claim 25, wherein said metal layer provides a ground plane for
30 said electrical connections.

27. The package of claim 26, wherein said semiconductor device is located between said metal layer and said dielectric substrate.

28. The package of claim 25, wherein said metal layer is arranged to dissipate heat from said semiconductor device.

29. The package of claim 25, wherein said metal layer comprises copper.

30. The package of claim 25, wherein said connections comprise wire bonds.

31. The package of claim 25, wherein said connections comprise conductive vias.

32. The package of claim 31, wherein said connections further comprise conductive traces on opposite sides of said substrate.

33. The package of claim 32, further comprising solder bumps on said semiconductor device, said bumps being connected to said traces.

34. The package of claim 24, further comprising an insulative solder mask for covering said dielectric substrate.

35. A method of handling a plurality of semiconductor devices arrayed in a semiconductor wafer, comprising:

adhering said wafer to a flexible substrate;

connecting said semiconductor devices to respective ball grid arrays located on said flexible substrate; and

testing said semiconductor devices through said ball grid arrays.

36. The method of claim 35, further comprising the step of identifying defective packages.

37. The method of claim 35, further comprising the step of singulating packages from said wafer and said substrate.

38. The method of claim 37, further comprising the step of segregating defective
5 packages from other packages.

ABSTRACT

A method of making semiconductor device packages includes the steps of attaching a wafer to a dielectric layer, testing semiconductor devices in the wafer, and then dicing the layered assembly. The dielectric layer may be, for example, a flexible tape. The semiconductor devices may be chips containing integrated circuits or memory devices. The dicing operation may be performed by a circular saw or by another suitable apparatus. The chips may be connected to input/output devices, such as ball grid arrays, on the dielectric layer, before the testing and dicing steps. Full wafer testing may be conducted through the ball grid arrays. A relatively stiff metal sheet may be included in the layered assembly before the testing and dicing steps. The metal material may be used as heat spreaders and/or as electrical ground planes. The chips may be connected to the ball grid arrays by wire bonds or flip chip bumps and vias through the dielectric layer. Alignment of the wafer with respect to the dielectric tape may be accomplished by an optical device or by a magnetic system.

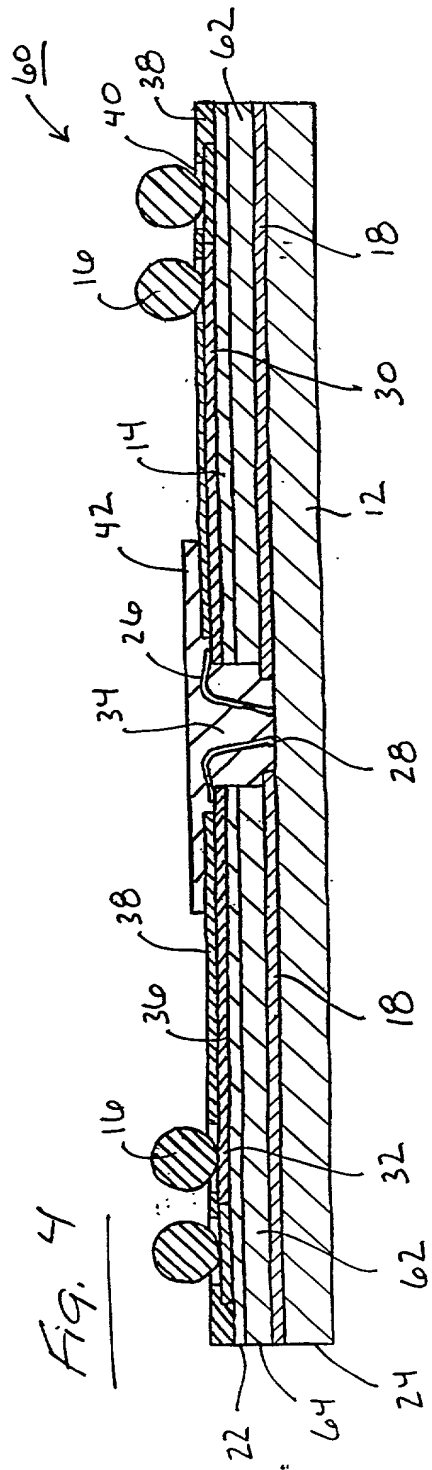
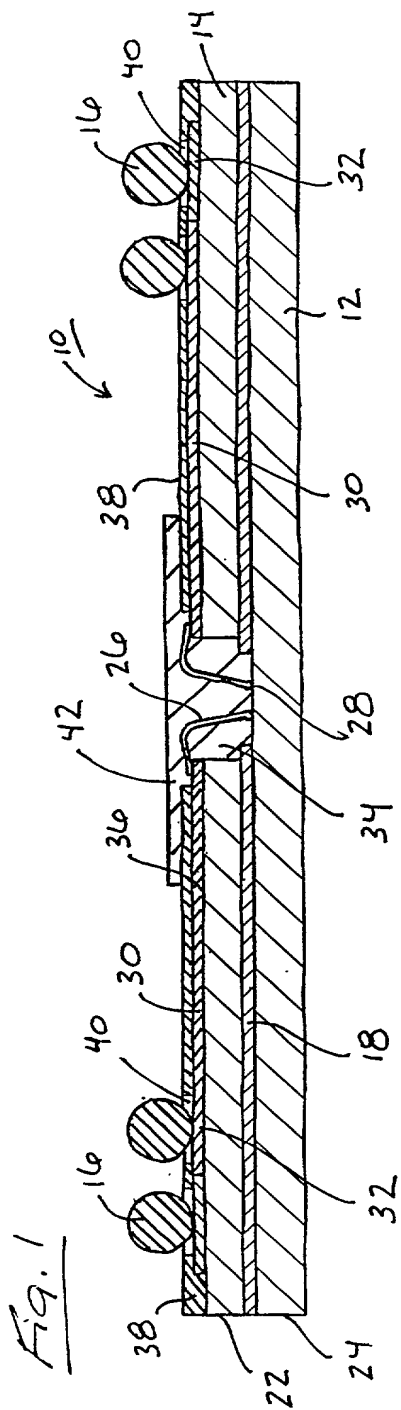


Fig. 2

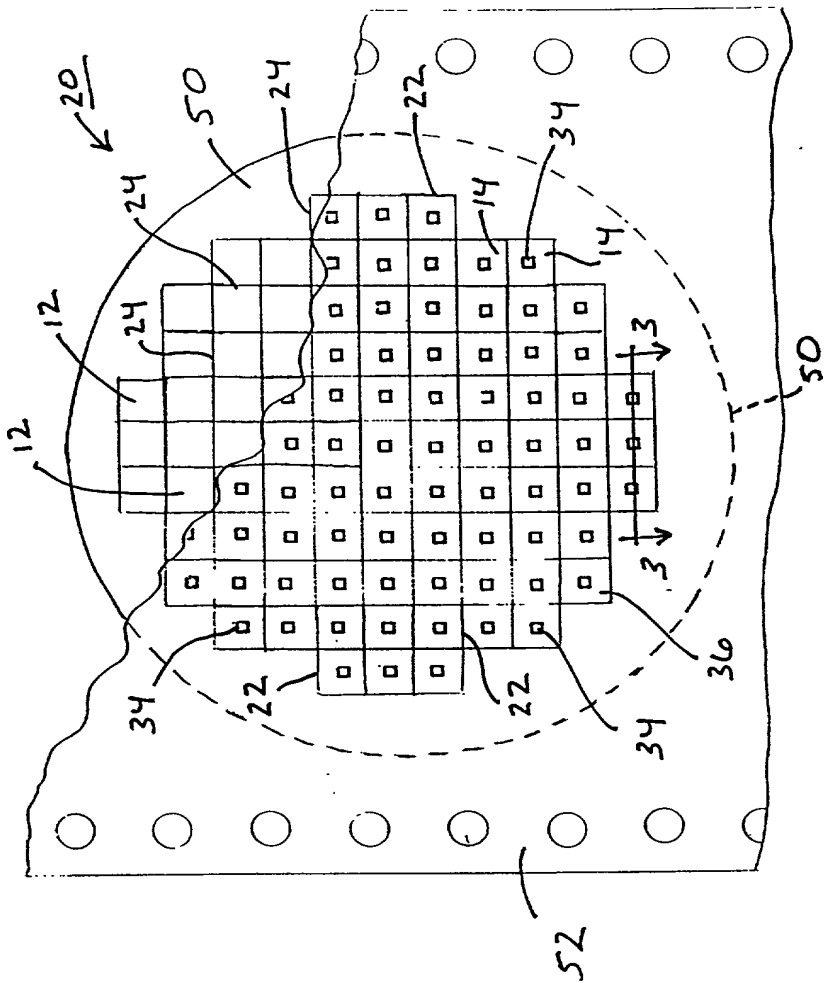


Fig. 3

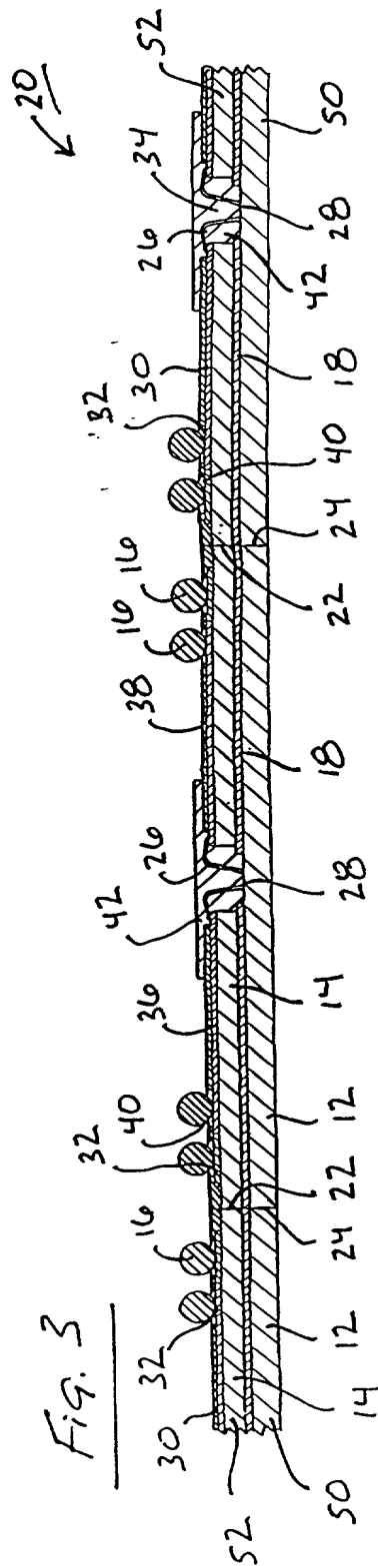


Fig. 6

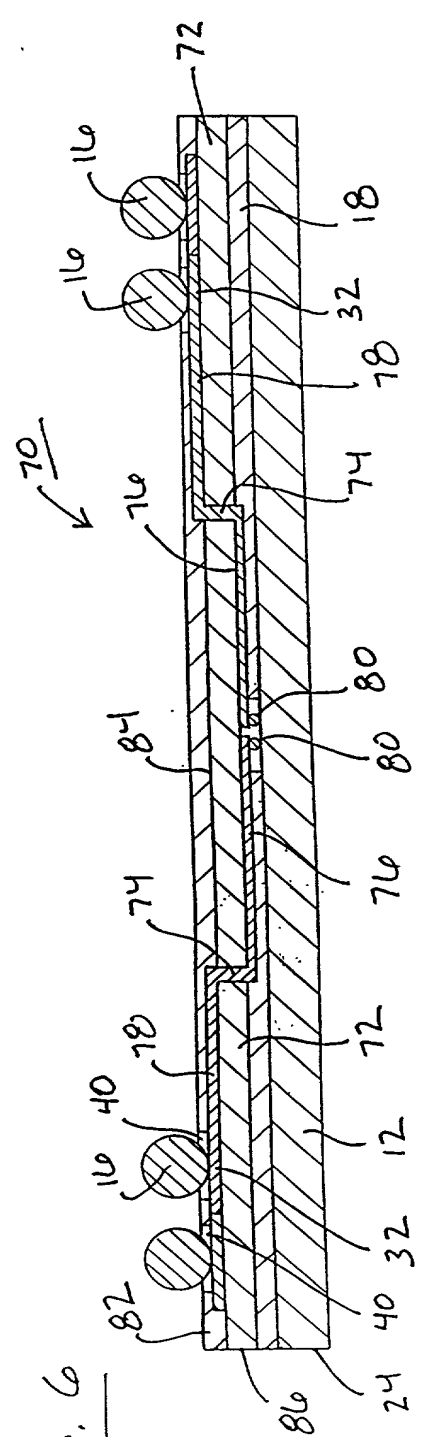


Fig. 7

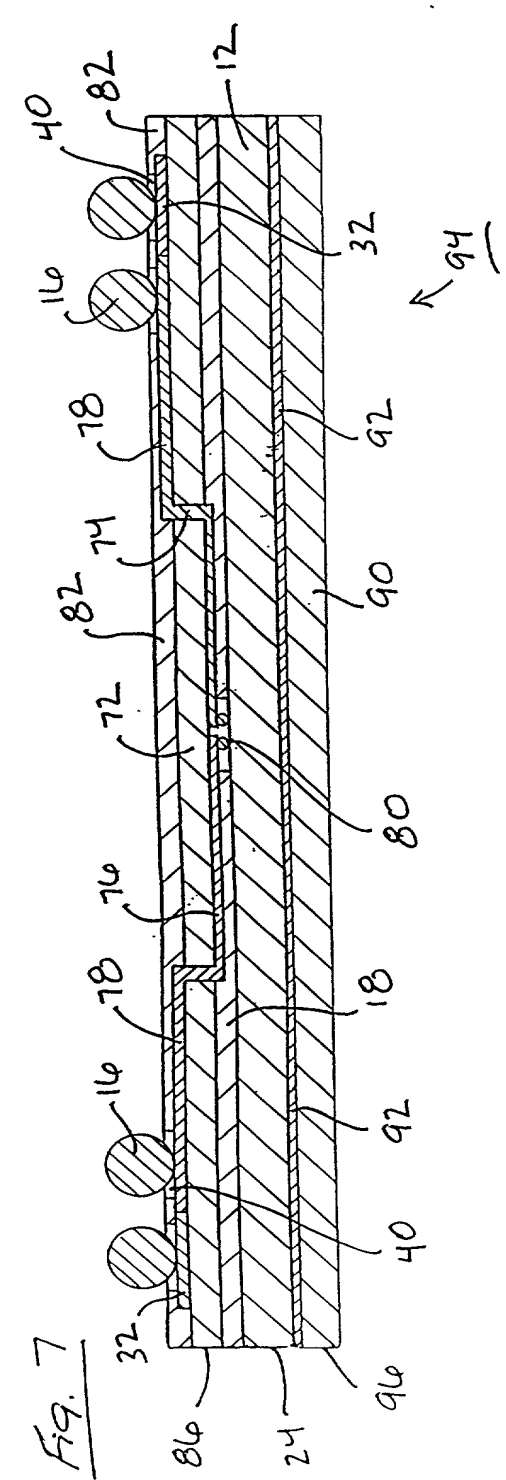
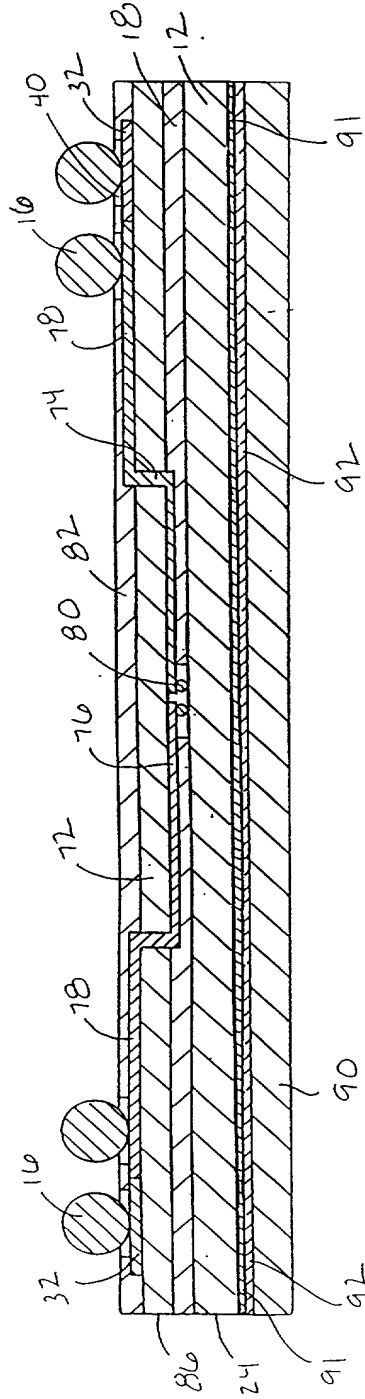


Fig. 8



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Alan G. Wood et al.

Serial No.: Not Yet Assigned

Group Art Unit: Not Yet Assigned

Filed: Concurrently Herewith

Examiner: Not Yet Assigned

For: THERMALLY ENHANCED
PACKAGE AND METHOD FOR
MANUFACTURING IT

Assistant Commissioner for Patents
Washington, D.C. 20231

**POWER OF ATTORNEY BY ASSIGNEE AND
CERTIFICATE BY ASSIGNEE UNDER 37 CFR § 3.73(b)**

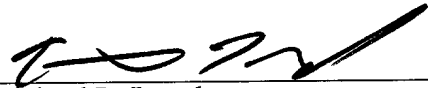
Micron Technology, Inc., assignee of the entire right, title and interest in the above-identified application by virtue of the assignment attached hereto (which is also being submitted concurrently for recordation), hereby appoints the attorneys and agents of the firm of Dickstein Shapiro Morin & Oshinsky LLP located at 2101 L Street NW, Washington DC 20037-1526, listed as follows: Gary M. Hoffman, 26,411; Thomas J. D'Amico, 28,371; Donald A. Gregory, 28,954; James W. Brady, Jr., 32,115; Jon D. Grossman, 32,699; Mark J. Thronson, 33,082; Laurence E. Fisher, 37,131; John R. Fuisz, 37,327; Brian A. Lemm, 43,748; Gianni Minutoli, 41,198; Eric Oliver, 35,307; William E. Powell, III, 39,803; James M. Silbermann, 40,413 and Salvatore P. Tamburo, P-45,153, and also attorneys of Micron Technology, Inc. as its attorneys with full power of substitution to prosecute this application and to transact all business in the Patent and Trademark Office in connection therewith.

The assignee certifies that the above-identified assignment has been reviewed and to the best of the assignee's knowledge and belief, title is in the assignee.

Please direct all correspondence regarding this application to the following:

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Dated: 6-12-00

Docket No.: M4065.0184/P184

Micron No.: 99-00132

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**DECLARATION FOR PATENT APPLICATION**

As a below named inventor, I hereby declare that:

My residence, post office address and citizenship are as stated below next to my name.

I believe I am an original, first and joint inventor of the subject matter which is claimed and for which a patent is sought on the invention entitled:

SEMICONDUCTOR DEVICE PACKAGE AND METHOD

The specification of which is attached hereto.

I hereby state that I have reviewed and understand the contents of the above identified specification, including the claims, as amended by an amendment, if any, specifically referred to in this oath or declaration.

I acknowledge the duty to disclose all information known to me which is material to patentability as defined in Title 37, Code of Federal Regulations, § 1.56.

I hereby claim foreign priority benefits under Title 35, United States Code §119/365 of any foreign application(s) for patent or inventor's certificate listed below and have also identified below any foreign application for patent or inventor's certificate having a filing date before that of the application on which priority is claimed:

Prior Foreign Application(s)			Priority Not Claimed
_____ (Number)	_____ (Country)	_____ (Filing Date)	<input type="checkbox"/>
_____ (Number)	_____ (Country)	_____ (Filing Date)	<input type="checkbox"/>
_____ (Number)	_____ (Country)	_____ (Filing Date)	<input type="checkbox"/>

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I hereby claim the benefit under Title 35, United States Code, § 120/365 of any United States and PCT international application(s) listed below and, insofar as the subject matter of each of the claims of this application is not disclosed in the prior United States application in the manner provided by the first paragraph of Title 35, United States Code, § 112, I acknowledge the duty to disclose all information known to me to be material to patentability as defined in Title 37, Code of Federal Regulations, § 1.56(a) which became available between the filing date of the prior application and the national or PCT international filing date of this application:

(Application Serial No.)	(Filing Date)	(Status) (patented, pending, abandoned)
(Application Serial No.)	(Filing Date)	(Status) (patented, pending, abandoned)
(Application Serial No.)	(Filing Date)	(Status) (patented, pending, abandoned)

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

Please address all correspondence to William E. Powell III of Dickstein Shapiro Morin & Oshinsky LLP located at 2101 L Street NW, Washington, DC 20037-1526. Telephone calls should be made to (202) 785-9700.

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
DECLARATION FOR PATENT APPLICATION

Signature Page for Second Inventor

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